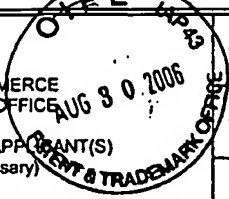


FORM PTO 1449 (modified)				ATTY DOCKET NO. 03500.017731.		APPLICATION NO. 10/533,091	
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				APPLICANT HIDEYA KUMOMI, ET AL.			
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)				FILING DATE April 28, 2005		GROUP 2812	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
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		5,207,863	05/04/93	Kumomi	156	603	—
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AL		5,723,348	03/03/98	Kumomi et al.	437	23	—
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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
AR	JP	8-8197	01/12/96	Japan	—		Abstract
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AR		Kumomi, et al. "Selective Nucleation-based Epitaxy (SENTAXY): A novel Approach for Thin Film Formation"; JPN J. Appl. Phys., Vol. 36 pp 1383-1388 (1997).					
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 1 of 1

JC12 Rec'd PCT/PTC 28 APR 2005

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			APPLICANT: HIDEYA KUMOMI				
			FILING DATE Herewith April 28, 2005		GROUP NYA 2812		

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AR		4,564,403	1/1986	Hayafuji et al.	148	171	_____
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		5,318,661	6/1994	Kumomi et al.	_____	_____	_____
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AR	GB	2338342	12/199	United Kingdom	_____	_____	Corresp to USP 6,326,286
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EXAMINER <i>AR</i>	DATE CONSIDERED 09/20/07
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